



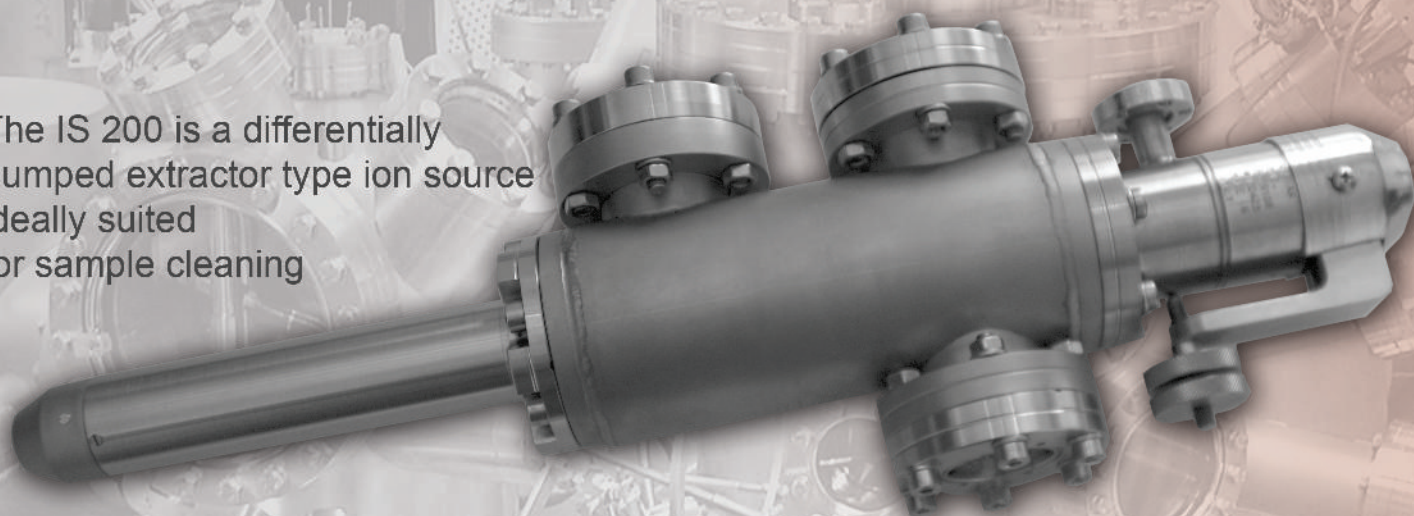
OmniVac

Surface Analysis and Vacuum Technology

Ion Source

IS 200

The IS 200 is a differentially pumped extractor type ion source ideally suited for sample cleaning



■ reactive gas sputtering

■ differential pumping

■ XY-deflection

■ energy range 0.2 - 3 keV

■ low cost

■ variable small spot size

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IS 200 Ion Source

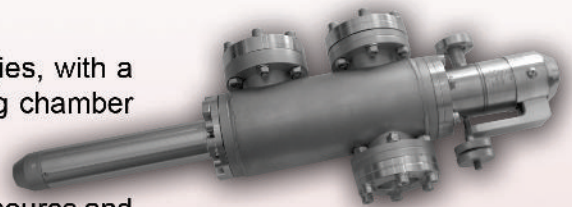
The **IS 200** is a differentially pumped extractor type ion source ideally suited for sample cleaning.

The low cost source's sturdy design guarantees stable operating conditions over a long period of time, even with the use of reactive gases.

Small spot sizes and a XY-deflection unit (± 5 mm) also allow for cleaning SPM tips.

High emission currents are provided even at low beam energies, with a primary energy range reaching from 0.2 to 3 keV and working chamber pressures as low as 10^{-8} mbar.

Spot size and current density depend on the distance between source and sample, where the overall length of the **IS 200** can be chosen to meet the specific requirements of the concerning **UHV chamber**.



Design

Primary energy range

Total current (FWHM -0.5 mm)

Working pressure

Spot size (FWHM)

Mounting flange

Insertion depth

Working distance

Bakeable

Differentially pumped extractor type ion source with XY-deflection unit

0.2 - 3 keV

15 μ A

down to 10^{-8} mbar

500 μ m (at 30 mm working distance)

DN 35 CF

variable

variable

up to 250°C

▶ energy range
0.2 - 3 keV

▶ variable small spot size

▶ XY-deflection unit

▶ reactive gas sputtering

▶ efficient sample cleaning

Related products:

IS 100 Ion Source, 0.2 - 5 kV

IS 300 Ion Source, 0.2 - 5 kV, XY-deflection, focus unit

PS-IS 200 Power Supply

Display

Ion energy, extractor voltage, emission current, deflection voltages

Dimension (W x H x D)

19" x 133 mm x 415 mm



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